

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS

LIST OF ART CITED BY APPLICANT

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
AA	4,024,400	5/77	05/13/77	Blytas et al.	250	432	05/13/76
AB	4,328,464		05/04/82	Pivrotto	330	4.3	02/07/80
AC	4,700,371		10/13/87	Forsyth et al.	378	34	11/08/84
AD	4,723,262		02/02/88	Noda et al.	378	119	12/26/85
AE	4,866,517		09/12/89	Mochizuke et al.	378	119	09/10/87
AF	4,953,191		08/28/90	Smither et al.	378	143	07/24/89
AG	5,126,755		06/30/92	Sharpe et al.	346	75	03/26/91
AH	5,142,297		08/25/92	Eijkman et al.	346	1.1	03/26/90
AI	5,148,462		09/15/92	Spitsyn et al.	378	143	04/08/91
AJ	5,151,928		09/29/92	Hirose	378	119	08/20/91
AK	5,243,638		09/07/93	Wang et al.	378	119	03/10/92
AL	5,257,303		10/26/93	Das Gupta	378	85	08/03/92
AM	5,459,771		10/17/95	Richardson et al.	378	119	04/01/94
AN	5,577,091		11/19/96	Richardson et al.	378	119	01/13/95
AO	5,577,092		11/19/96	Kublak et al.	378	119	11/19/96
AP	5,991,360		11/23/99	Matsui et al.	378	119	02/03/98
AQ	6,002,744		12/14/99	Hertz et al.	378	119	10/21/98

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6/15/06

FOREIGN PATENT DOCUMENTS

CT	FA	JP 57/41167	03/1982	
↓	FB	JP 0267895	11/90	Iwamatsu

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